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Total Number of Pages in This Submission

Application Number	10/694,284
Filing Date	October 27, 2003
First Named Inventor	Frank Y. Xu
Art Unit	Unassigned
Examiner Name	Unassigned
Attorney Docket Number	PA94-36-03

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Xu et al.

PATENT APPLICATION

Serial No.: 10/694,284

Group Art Unit: Unassigned

Filing Date: 10/27/2003

Examiner: Unassigned

For: METHODS FOR FABRICATING PATTERNED FEATURES UTILIZING
IMPRINT LITHOGRAPHY.

INFORMATION DISCLOSURE STATEMENT

Commissioner
for Patents
Alexandria, VA 22313-1450

Sir:

The following information is submitted in compliance with Applicants' duty of disclosure under 37 C.F.R. § 1.56. Form PTO-1449 and the requisite copies of each reference recited below accompanies this document. It is respectfully requested that the cited information be expressly considered during the prosecution of this application, and the references be made of record therein and appear among the "references cited" on any patent to issue therefrom.

ISSUED PATENTS

<u>Patent Number</u>	<u>Inventor</u>	<u>Grant Date</u>
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OTHER PATENT DOCUMENTS

<u>Application Number</u>	<u>Inventor</u>	<u>Filing Date</u>
09/698,317	Choi et al.	10/27/2000
10/264,926	Sreenivasan et al.	10/04/2002
10/396,615	Sreenivasan et al.	03/25/2003
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PATENT APPLICATION PUBLICATIONS

<u>Publication Number</u>	<u>Inventor</u>	<u>Publication Date</u>
US 2002/0098426	Sreenivasan et al.	07/25/2002
US 2002/0094496	Choi et al.	07/18/2002
US 2003/0093122	Choi et al.	07/18/2002
US 2003/0235787	Watts et al.	12/25/2003
US 2004/0010341	Watts et al.	01/15/2004
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<u>Document No.</u>	<u>Inventor</u>	<u>Pub. Date</u>
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Nguyen, A. Q. "Asymmetric Fluid-Structure Dynamics in Nanoscale Imprint Lithography," University of Texas at Austin, August 2001.

Bender M. et al., "Fabrication of Nanostructures Using A UV-based Imprint Technique," *Microelectronic Engineering*, pp. 223-236, 2000

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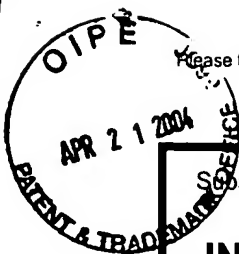
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Sheet 3 of 5

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Application Number	10/694,284
Filing Date	10/27/2003
First Named Inventor	Xu et al.
Group Art Unit	Unassigned
Examiner Name	Unassigned
Attorney Docket Number	PA94-36-03

OTHER PRIOR ART – NON PATENT LITERATURE DOCUMENTS

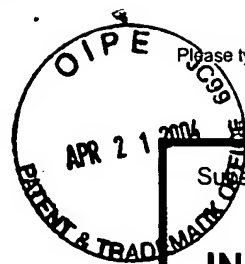
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	A22	Krauss et al., "Fabrication of Nanodevices Using Sub-25nm Imprint Lithography," Appl. Phys. Lett 67(21), 3114-3116, 1995	
	A23	CHOU et al., "Imprint of Sub-25 nm Vias and Trenches in Polymers," Applied Physics Letters, November 20, 1995, pp. 3114-3116, vol. 67(21).	
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	A26	CHOU et al., "Imprint Lithography with Sub-10nm Feature Size and High Throughput," Microelectronic Engineering, 1997, pp. 237-240, vol. 35.	
	A27	XIA et al., "Soft Lithography," Annu. Rev. Mater. Sci., 1998, pp. 153-184, vol. 28.	
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Application Number	10/694,284
Filing Date	10/27/2003
First Named Inventor	Xu et al.
Group Art Unit	Unassigned
Examiner Name	Unassigned
Attorney Docket Number	PA94-36-03

OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS

Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
	A33 /	CHOU, "Nanoimprint Lithography and Lithographically Induced Self-Assembly," MRS Bulletin, July 2001, pp. 512-517.	
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Application Number	10/694,284
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First Named Inventor	Xu et al.
Group Art Unit	Unassigned
Examiner Name	Unassigned
Attorney Docket Number	PA94-36-03

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Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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